

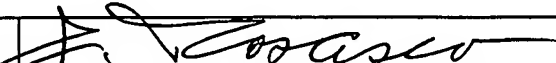


Substitute for Form 1449 A & B/PTO  <b><u>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</u></b> <i>(use as many sheets as necessary)</i>				<i>Complete if Known</i>	
				Application Number	10/519,991
				Confirmation Number	9188
				Filing Date	January 4, 2005
				First Named Inventor	Shinichi ISHIBASHI
				Art Unit	1795
				Examiner Name	Stephen D. Rosasco
Sheet	1	of	1	Attorney Docket Number	Q85552

U.S. PATENT DOCUMENTS					
Examiner Initials*	Cite No. <sup>1</sup>	Document Number		Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document
		Number	Kind Code <sup>2</sup> (if known)		
		US			
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FOREIGN PATENT DOCUMENTS							
Examiner Initials*	Cite No. <sup>1</sup>	Foreign Patent Document			Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Translation <sup>6</sup>
		Country Code <sup>3</sup>	Number <sup>4</sup>	Kind Code <sup>5</sup> (if known)			

NON PATENT LITERATURE DOCUMENTS			
Examiner Initials*	Cite No. <sup>1</sup>	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city, and/or country where published.	Translation <sup>6</sup>
		Ted LIANG, et al. "ENHANCED OPTICAL INSPECTABILITY OF PATTERNED EUVL MASK", Intel Corporation Components Research, Proceedings of SPIE Vol. 4562 (2002), pgs. 288-296.	
		Semiconductor Equipment and Materials International SEMI Draft Document 3414 "SPECIFICATION FOR ABSORBING FILM STACKS AND MULTILAYERS ON EXTREME ULTRAVIOLET LITHOGRAPHY MASK BLANKS" Document Number 3414 dated 04/29/2002.	

Examiner Signature		Date Considered	1/08
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\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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